

PART 8: Stripping

Aqueous Caustic (NaOH or KOH) ConveyORIZED Stripping

Note:

- Dwell Time = 2x Time to strip resist
- High caustic concentrations produce larger skin sizes and higher loading capabilities.

Stripper Dwell Times (seconds) at 55°C
(130°F), 1.7 kg/cm² (25psig), Over
Recommended Exposure Range

	<u>215</u>	<u>220</u>
1.5 wt% NaOH	80 -110 sec	150 -190 sec
3.0 wt% NaOH	60 - 80	100 -120
1.5 wt% KOH	110 -140	120 -170
3.0 wt% KOH	50 -70	90-110